



US 20220368301A1

(19) **United States**(12) **Patent Application Publication**
FUKUMITSU et al.(10) **Pub. No.: US 2022/0368301 A1**(43) **Pub. Date: Nov. 17, 2022**(54) **METHOD OF MANUFACTURING
COLLECTIVE SUBSTRATE AND
COLLECTIVE SUBSTRATE****Publication Classification**(51) **Int. Cl.****H03H 3/007** (2006.01)**H03H 9/10** (2006.01)**H03H 9/24** (2006.01)(52) **U.S. Cl.****CPC** **H03H 3/0072** (2013.01); **H03H 9/1057**
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filed on Nov. 11, 2020.(30) **Foreign Application Priority Data**

Apr. 9, 2020 (JP) 2020-070182

(57)

ABSTRACT

A method of manufacturing a collective substrate that includes: forming at least one first mark in or on a first main surface of a first substrate; joining the first main surface of the first substrate and a first main surface of a second substrate to each other; forming an opening in the second substrate such that the first mark is exposed therein; and forming a device portion in or on a second main surface of the second substrate while using the first mark as a reference.

